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(12) **United States Design Patent**
Chen

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(54) **MASK**

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(**) **Term:** **14 Years**

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(51) **LOC (8) Cl.** **29-02**

(52) **U.S. Cl.** **D29/108**

(58) **Field of Classification Search** D29/102-110,
D29/122; 2/5, 6.1, 6.3, 6.5-6.7, 411, 414,
2/423-425, 431, 8-9, 427; 128/201.24, 206.21,
128/206.28; D24/110.1, 110.2, 110.3
See application file for complete search history.

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Primary Examiner—Ruth McInroy

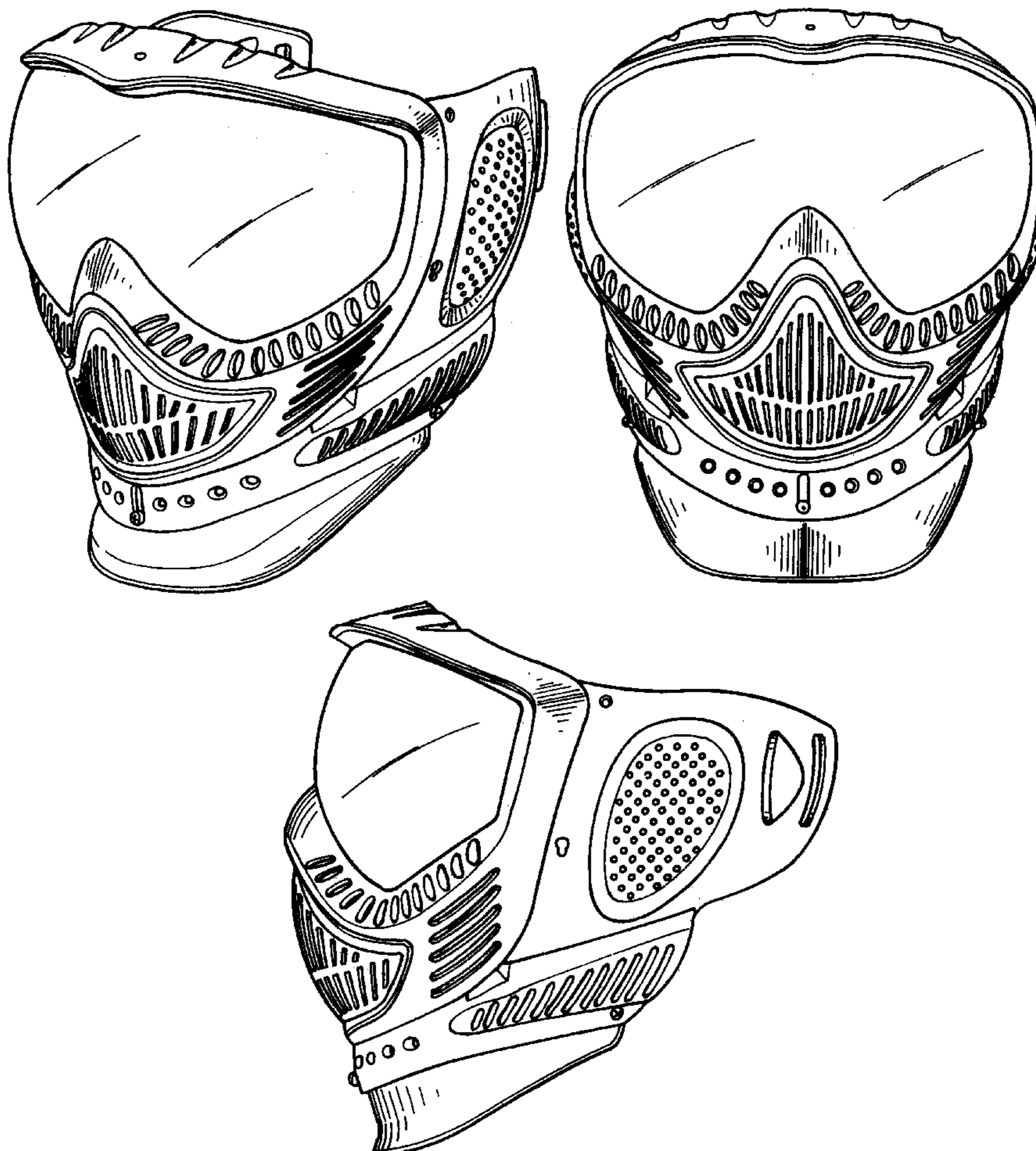
(57) **CLAIM**

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a mask showing my new design;
FIG. 2 is a front elevational view thereof;
FIG. 3 is a rear elevational view thereof;
FIG. 4 is a left side elevational view thereof;
FIG. 5 is a right side elevational view thereof;
FIG. 6 is a top plan view thereof; and,
FIG. 7 is a bottom plan view thereof.

1 Claim, 4 Drawing Sheets



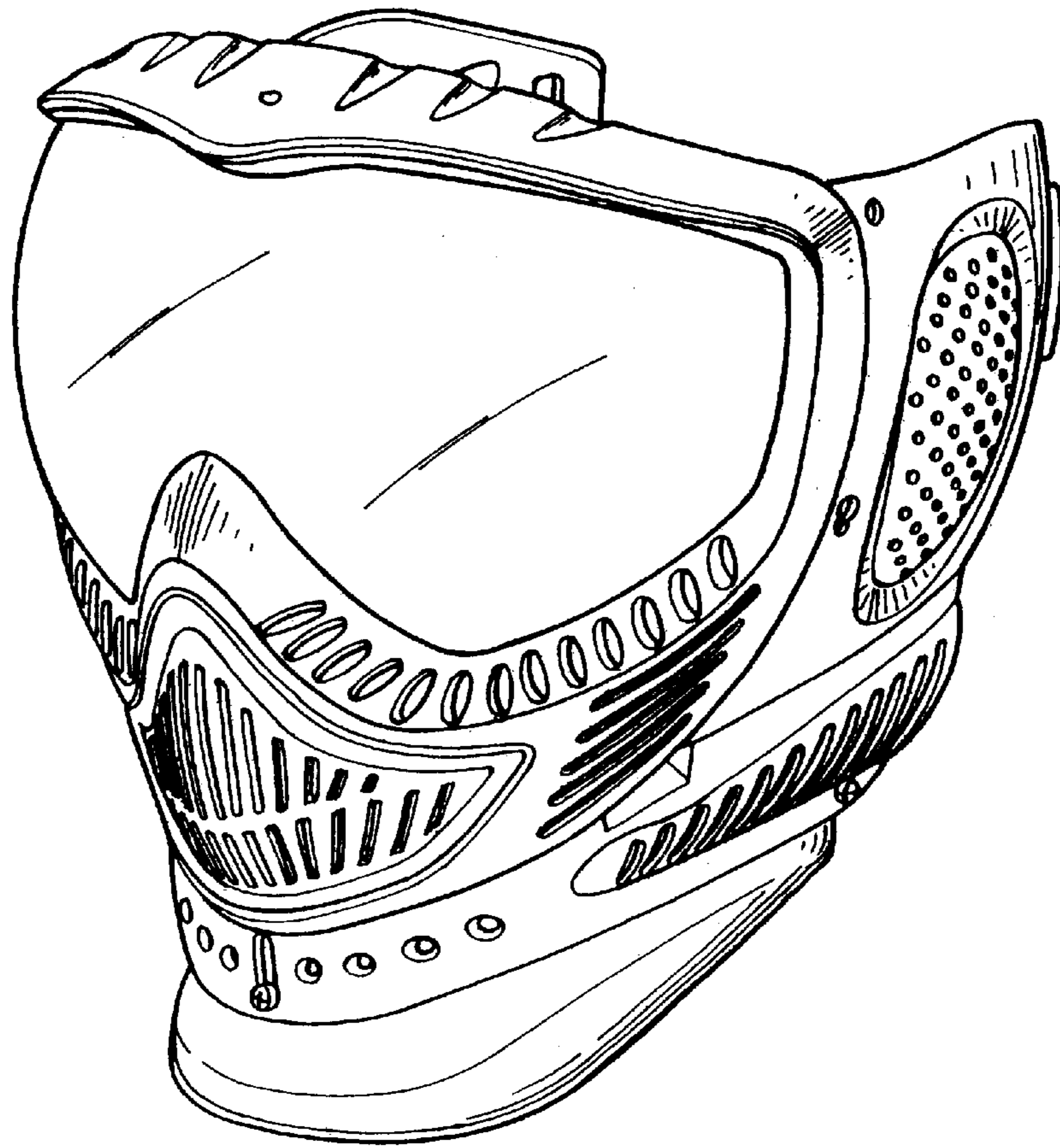


FIG.1

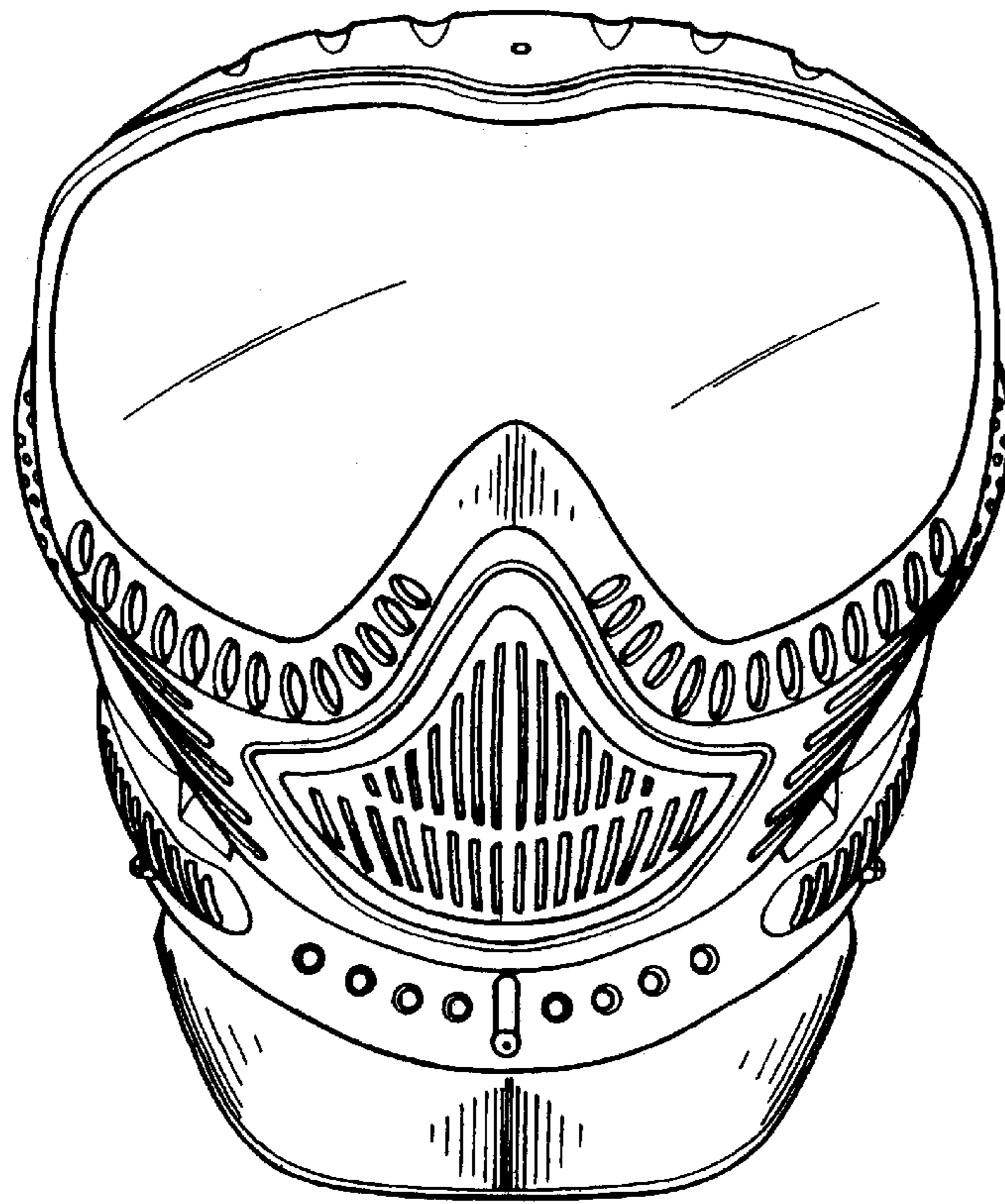


FIG. 2



FIG. 3

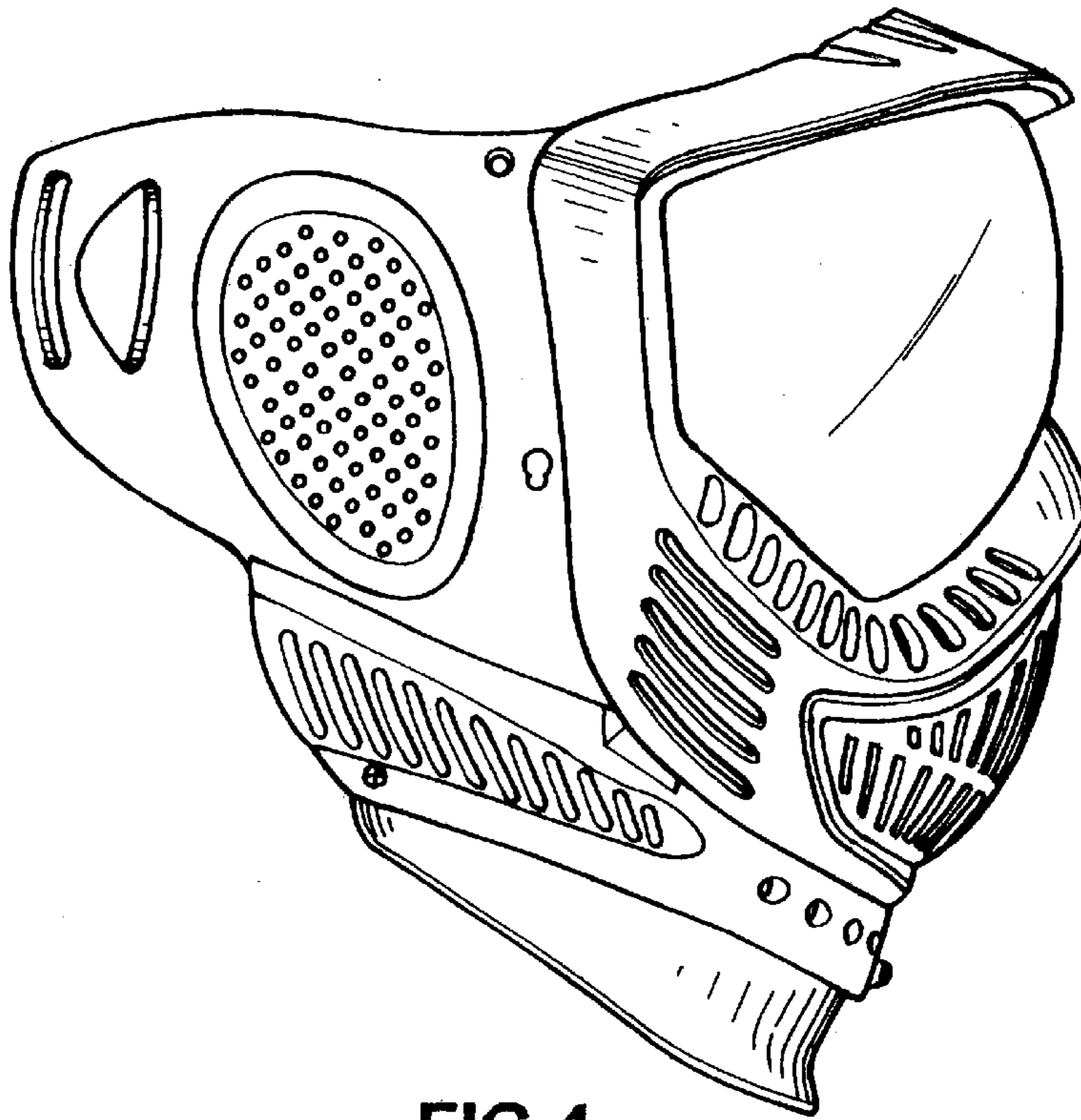


FIG. 4

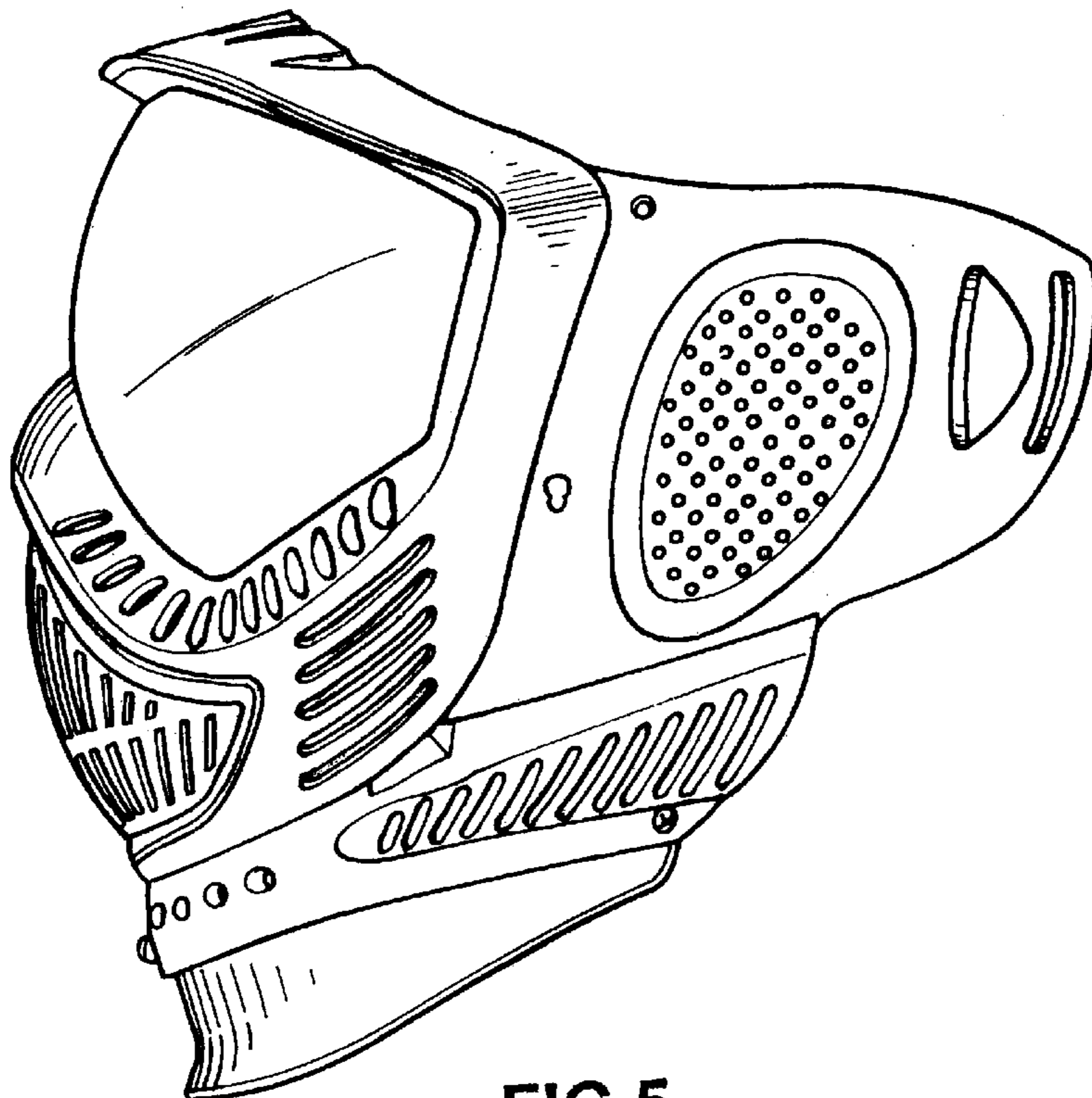


FIG. 5

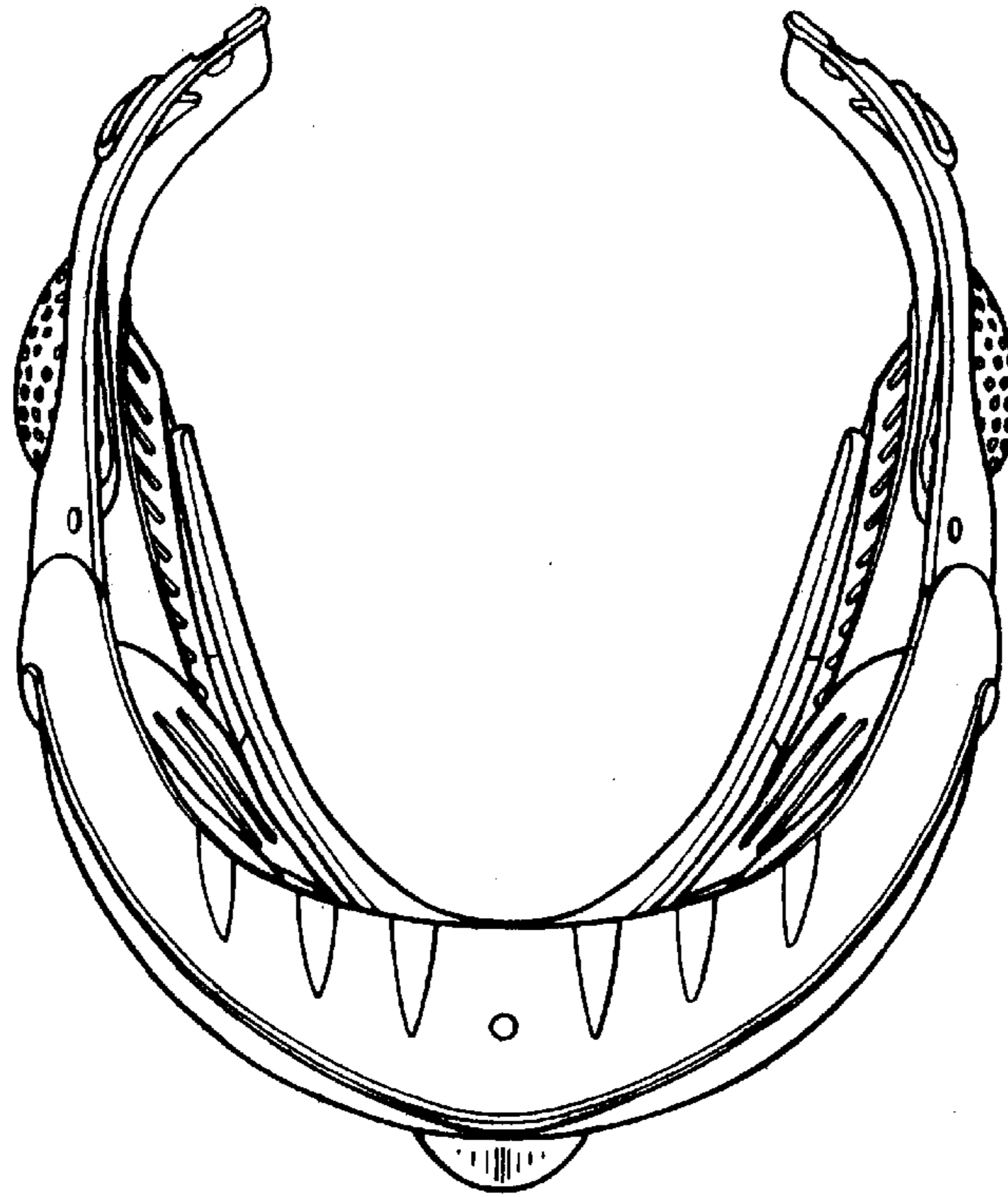


FIG. 6

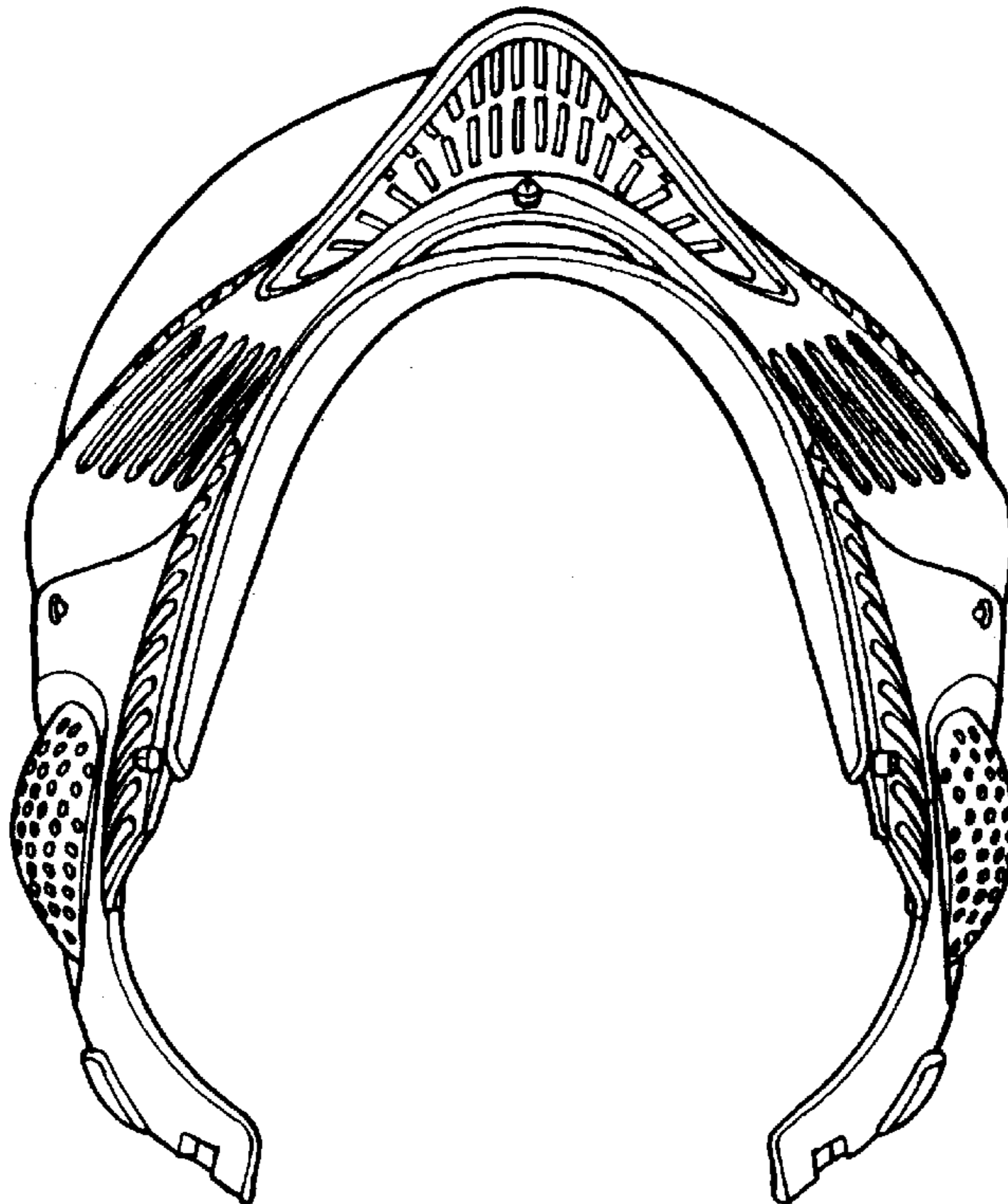


FIG. 7